

C^v 64. (Amended) A projection optical system according to claim 63, wherein said plurality of lenses further includes an another aspherical lens surface with refractive power at a paraxial region and refractive power at a periphery, and wherein said refractive power at said periphery is stronger than said refractive power at said paraxial region.

Please add new claims 104-111 as follows:

--104. (New) A projection optical system according to claim 54, wherein the plurality of lenses include a first positive group of lenses, a second positive group of lenses, and a negative group of lenses arranged in an optical path between the first positive group of lenses and the second positive group of lenses,

wherein the second positive group of lenses having the aperture stop and at least two lenses is arranged in an object side optical path of the aperture stop.--

C³ --105. (New) A projection optical system according to claim 104, wherein the first positive group of lenses includes a negative lens, and the second positive group of lenses includes a negative lens.--

--106. (New) A projection optical system according to claim 105, wherein the negative lens in the first positive group of lenses is arranged most objectwise.--

--107. (New) A projection optical system according to claim 104, wherein the plurality of lenses includes an aspherical lens surface.--

--108. (New) A projection optical system according to claim 107, wherein the plurality of lenses further includes an additional negative group of lenses arranged in an optical path between the first positive group of lenses and the second positive group of lenses, and a third positive group of lenses arranged in an optical path between the negative group of lenses and the additional negative group of lenses.--

--109. (New) A projection optical system according to claim 104, wherein the exposure field has a dimension of at least 25mm.--

--110. (New) A scanning projection exposure apparatus for projecting an image of a pattern on a reticle onto a photosensitive workpiece, comprising:

a first stage that is movable along a scanning direction and supports the reticle at a first surface;

an illuminating optical system adjacent the first stage and arranged so as to illuminate the reticle with a light;

a second stage that is movable along at least the scanning direction and supports the photosensitive workpiece at a second surface; and

a projection optical system according to claim 54 arranged in an optical path between the first surface and the second surface.--

--111. A method of patterning a photosensitive workpiece with a pattern present on a reticle, comprising the steps of:

illuminating the reticle;
projecting the light from the reticle with a projection optical system according to claim 54; and

exposing the photosensitive workpiece over the exposure field.--

REMARKS

By this Amendment, claims 60 and 64 are amended, claims 16-18, 31, 32, 38-53 and 67-103 are canceled and new claims 104-111 are added. Accordingly, claims 54-66 and 104-111 are pending. No new matter is added.

The attached Appendix includes marked-up copies of each rewritten claim (37 C.F.R. 1.121(c)(1)(ii)).

New claims 104-109 read on the elected Group. New claims 110 and 111 depend from elected claim 54 and should be rejoined upon allowance of claim 54.